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PATENT
Attorney Docket No.: 16301T-034100US
Client Ref. No.:
004182/ETCH/DRIE/JB1

Commission for Patents
PO Box 1450
Alexandria, VA 22313-1450

On 5/7/03

TOWNSEND and TOWNSEND and CREW LLP

By: R. Faires

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GROUP 1700

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Liang-Guo Wang et al.

Application No.: 09/767,282

Filed: January 22, 2001

For: RF POWER DELIVERY FOR
PLASMA PROCESSING USING
MODULATED POWER SIGNAL

Examiner: Parviz Hassanzadeh

Art Unit: 1763

AMENDMENT

#14A
5/16/03
mw

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action mailed January 8, 2003, please amend the above-identified application as follows:

IN THE SPECIFICATION

Please replace the paragraph beginning at page 1, line 13 with the following paragraph.

--It is desirable to increase the number of controllable processing parameters in a plasma processing apparatus. More controllable process parameters provide process engineers with more ways to control the operation of the apparatus to optimize a given

A1